

AMENDMENTS TO THE CLAIMS:

Please cancel Claims 2, 4, 5, 6 and 7 without prejudice to or disclaimer of the subject matter recited therein.

Please amend Claim 1 as follows:

1. (Currently Amended) A method of manufacturing an optical element comprising at least a plurality of pixels formed on a substrate and partition walls arranged respectively between adjacent pixels, said method comprising the steps of:

forming partition walls from a resin composition containing carbon black on a substrate;

performing a dry etching process by irradiating the substrate carrying said partition walls formed thereon with plasma in an atmosphere containing a gas selected from the group consisting of oxygen, argon, and helium;

performing a plasma treatment process by irradiating the substrate subjected to said dry etching process with plasma in an atmosphere formed by introducing a mixture of (a) a halogen gas selected from the group consisting of CF₃, SF₆, CHF₃, C₂F₅, C₃F₈, and C₄F₈ and (b) O₂ gas, wherein the amount of O₂ gas in the mixture is not greater than 30% such that each partition wall after said plasma treatment process shows a surface having a contact angle relative to pure water of not smaller than 110° and a surface coarseness represented by an arithmetic mean deviation (Ra) of between 3nm and 50nm which is greater than before said dry etching process and such that the substrate after said plasma

treatment process shows a surface having a contact angle relative to pure water, of not greater than 20°;

forming pixels by applying ink containing at least a setting ingredient, water, and an organic solvent to the areas surrounded by the partition walls by means of an ink-jet system; and
setting the applied ink.

2 - 8. (Cancelled)

9. (Previously Presented) The method of manufacturing an optical element according to claim 1, wherein said method is adapted to manufacture a color filter where said substrate is a transparent substrate and said partition walls are provided by a black matrix.

10. (Cancelled)

11. (Previously Presented) The method of manufacturing an optical element according to claim 1, wherein after said plasma treatment process, the plasma-treated substrate is subjected to a water treatment process.

12. (Cancelled)